

Docket No.: EHF 2001,0167 P

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231, on the date indicated below.

By: RP

Date: 8/17/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Norbert Benesch et al.
Applic. No. : 09/873,230
Filed : June 4, 2001
Title : Method and Device for Optically Monitoring Fabrication Processes of Finely Structured Surfaces in a Semiconductor Production

INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner of Patents and Trademarks,
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

United States Patent No. 4,964,726 (Kleinknecht et al.), dated October 23, 1990;

United States Patent No. 5,703,692 (McNeil et al.), dated December 30, 1997;

United States Patent No. 5,830,611 (Bishop et al.), dated November 3, 1998;

German Published, Non-Prosecuted Patent Application DE 198 24 624 A1 (Bischoff), dated February 25, 1999, measuring arrangement for optical diffraction analysis of periodic sub micrometer structures;

European Patent Application EP 0 874 396 A2 (Waldhauer et al.), dated October 28, 1998;

Scott Bushman et al.: "Scatterometry Measurements for Process Monitoring of Polysilicon Gate Etch", SPIE, vol. 3213, 1997, pp. 79-90, XP-000890146;

Stephen A. Coulombe et al.: "Ellipsometric-Scatterometry for sub-0.1 μm CD measurements", SPIE, vol. 3332, 1998, pp. 282-293, XP-000890148;

Jörg Bischoff et al.: "Optical scatterometry of quarter micron patterns using neural regression", SPIE, vol. 3332, 1998, pp. 526-537, XP-000890149;

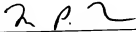
N. Benesch et al.: Application and cost analysis of scatterometry for integrated metrology", SPIE, vol. 3743, May 1, 1999, pp. 25-32, XP-000890150;

Michael R. Murnane et al.: "Developed photoresist metrology using scatterometry", SPIE, vol. 2196, March 1994, pp. 47-59, XP-000890152;

Ilkka Kallioniemi et al.: "Optical scatterometry of subwavelength diffraction gratings: neural-network approach", Applied Optics, vol. 37, No. 25, September 1, 1998, pp. 5830-5835, XP-000890173.

If no translation of pertinent portions of any foreign language patents or publications mentioned above is included with the aforementioned copies of those applications, patents and/or publications, it is because no existing translation is readily available to the applicant.

Respectfully submitted,



For Applicants

Mark P. Weichselbaum
Reg. No. 43,248

Date: August 17, 2001

Lerner And Greenberg, P.A.
Post Office Box 2480
Hollywood, FL 33022-2480
Tel: (954) 925-1100
Fax: (954) 925-1101
/bmb